

Erratum

In the article "Photochemical Decomposition Mechanisms for AZ-Type Photoresists" by J. Pacansky and J. R. Lysterla (*IBM J. Res. Develop.* **23**, No. 1, 42-55, 1979) AZ-1350J was incorrectly listed as a trademark of the Shipley Co., Newton, MA; ®AZ is a trademark of the Azoplate Division of American Hoechst Corporation, Somerville, NJ 08876.